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Morham et al.

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(54) **ANTIMICROBIAL FABRIC APPLICATION SYSTEM**

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(*) Notice: Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 247 days.

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A61L 2/00 (2006.01)
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CPC **D06F 39/022** (2013.01); **A01N 59/16** (2013.01); **D06M 23/10** (2013.01)

(58) **Field of Classification Search**
CPC A61L 2/00; A61L 2/18; A61L 2/26

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(57) **ABSTRACT**

An antimicrobial supply system employs a process water supply and incorporates a metallic ion supply connected to the process water supply to provide a high ion concentrate to an output. A dilution reservoir is connected to the metallic ion supply output and has an input from the process water supply. A pump is connected to an output of the reservoir. A manifold connected to the pump provides a dilute concentrate to at least one washing system. An electronics control module is connected to a first flow controller between the process water supply and the metallic ion supply and a second flow controller between the metallic ion supply and the reservoir for dilution control establishing a desired metallic ion concentration.

26 Claims, 16 Drawing Sheets

